



**Technical Conference Program (state October 7 – subject to change)**

**Day 1)**

Time	Day 1 - Monday, October 21	Speaker	Company / Institute
09:00	Exhibition set-up		
10:00	Registration		
11:00	Wine Tasting Tour		
	Posters can be set-up the whole day		
17:00	NIL Tutorial	Helmut Schiff	PSI
18:30	<b>Welcome Reception / Exhibition Area</b>		
19:30	NIL Survey	Stefan Landis	CEA
		Helmut Schiff	PSI



## Technical Conference Program Day 2)

		Day 2 - Tuesday, October 22	Speaker	Company / Institute
09:00		Opening Session C. Sotomayor Torres, Welcome from Spain, S. Chou and L. Montelius		
<b>Session #1 Large Area Processes Chairs TBA</b>				
09:30	Inv	Nanoimprint Technology for Large Area and Uniformity	Akihiro Miyauchi	Hitachi Ltd.
10:00	Inv	Photon Management in Solar Cells Based on Nanoimprint Lithography Processes	Benedikt Bläsi	FhG ISE
10:30	<b>Coffee Break</b>			
<b>Session #2 NIL for Production Chairs TBA</b>				
11:00		"Rolling Mask" Nanopatterning of Advance Glass Products	Ian McMackin	Rolith, Inc.
11:20		From research to small volume-production using soft-nanoimprint	van de Laar	Philips Innovation Services (PiNS)
11:40		High Bit-Aspect-Ratio Nanoimprint Templates for Bit Patterned Media with Critical Dimensions ~10nm or Less	He Gao	HGST, Western Digital Company
12:00		Accuracy of Wafer Level Alignment with Substrate Conformal Imprint lithography	Robert Fader	FhG IISB
12:20		Large-area micro/nano patterning on soluble block copolymer polyimide	Sung-Won Youn	National Institute of AIST
12:40		Sub-100 nm Channel P3HT-OFET Fabricated by Wafer-Scale Nanoimprint and its AC Test	Lichao Teng	TU Dresden
13:00	<b>Lunch</b>			
<b>Session #3 Applications 1 Chairs TBA</b>				
14:30	Inv	Nanoimprinted 'Bubble-wrap'	Hong Yee Low	SUTD
15:00		Large Area Micro-Structuring of Superhydrophobic Surfaces and Microfluidic Structures with Capillary-Driven Water Flow in Open Channels by Roll-to-Roll-UV-Imprint-Lithography	Dieter Nees	JOANNEUM RESEARCH
15:20		Self-assembled large area ordered nanodot arrays by solvent-assisted nanoimprint of a block copolymer	Claudio D. Simao	ICN2
15:40	Inv	Engineering Nanofluidic Devices for DNA Sequencing	Sunggook Park	Louisiana State University
16:10	<b>Coffee Break and Poster Session</b>			
<b>Session #4 Roll-to-Roll Chairs TBA</b>				
18:10	Inv	Nanoplasmonic Cavity Antenna Array for Giant Enhancements in Sensors, Solar Cells and LEDs	Steve Chou	Princeton University
18:40		Application areas for Roll to Roll Imprint Lithography in flexible electronics	Joris de Riet	Holst Centre/TNO
19:00		VIS Anti-reflection Nanostructure Film by Using Roll-to-Roll UV-Nanoimprint Technology	Chia-Hsing Liu	National Tsing Hua University
19:20		Fabrication of Device Structures using Hybrid Materials Sets and UV-Assisted Roll-to-Roll Nanoimprint Lithography	James J Watkins	U Massachusetts Amherst
20:00	<b>Conference Dinner</b> (Bus pick-up from the hotel at 20:00 hrs)			20:30 Restaurant Can Cortada (Bus pick-up to the hotel at 23:30 hrs)



**Technical Conference Program  
Day 3)**

Time		Day 3 - Wednesday, October 23	Speaker	Company/ Institute
<b>Industrial Session #5 Chairs TBA</b>				
09:00	Inv	Creativity with Polymers to form CHAINS: from Lab to Fab	Gabi Grütznér, Arne Schleunitz, Marko Vogler	micro resist technology GmbH
09:20	Inv	High-volume nanoscale imprinting	Doug Resnick	MII
09:40	Inv	Development of LED-PSS Fabrication Process by UV-Nanoimprint Lithography with Using Film Mold	Ryota Kojima	SOKEN Chemical & Engineering Co., Ltd.
10:00	Inv	Semiconductor Equipment Assessment for Nanoimprint: Opportunities and Challenges	Lothar Pfitzner	FhG IISB
10:20	Inv	Full wafer imprint lithography from R&D to high volume production	Ulrike Schömbbs	SUSS
10:40	Inv	Masters for production using nano-replication	Brian Bilenberg	NILT
11:00		<b>Coffee Break</b>		
<b>Session #6 Modelling and Process Chairs TBA</b>				
11:30		Modeling the mechanical deformation of PTFE flexible stamps for nanoimprint lithography on double-curved surfaces	Mads R Sonne	Technical University of Denmark
11:50		Simulation study on Template Releasing Process based on Cohesive Mechanics	Yoshihiko Hirai	Osaka Prefecture University
12:10		Curvature Prediction during Defined Reflow of Electron-beam Grayscale Profiles	Robert Kirchner	Paul Scherrer Institut
12:30		A chip-scale imprinter with integrated optical interference for calibrating models of NIL resists and resist-stamp boundary conditions	Hayden Taylor	Nanyang Technological University
12:50		Advances In Material Variety For Hot Embossing	Matthias Worgull	Karlsruhe Institute of Technology
13:10		<b>Lunch</b>		
<b>Session #7 Applications 2 Chairs TBA</b>				
14:30	Inv	Imprint technology in high volume VCSEL production	Alexander Weigl Co-Author: Marc Verschuuren	ULM Photonic Philips Research
15:00		Fundamental Study on Thermal Nanoimprint Process for Oxide-channel Thin Film Transistor Fabrication	Eisuke Tokumitsu	JAIST
15:20		Membranes and Tubules by Nanoimprinting and Atomic Layer Deposition	Tomi Haatainen	VTT
15:40		Microstructuration and protein patterning over modified glycosaminoglycans	Santos Merino	Tekniker
16:00	Inv	Colloidal Microfluidic: Technologies and Applications	David Peyrade	CNRS - LTM / CEA
16:30		Closing C. Sotomayor Torres, Next Conference Chair		
17:00		<b>End of Conference / Exhibition tear-down</b>		